



US00D789450S

(12) **United States Design Patent**  
**Maxted et al.**

(10) **Patent No.: US D789,450 S**  
(45) **Date of Patent: \*\* Jun. 13, 2017**

(54) <b>METROLOGY TRAINING DEVICE</b>	4,487,585 A * 12/1984 Goldwasser ..... A63F 9/10 273/156
(71) Applicant: <b>RENISHAW PLC</b> , Wotton-under-Edge, Gloucestershire (GB)	D397,382 S * 8/1998 Gensler ..... D21/648 D429,775 S * 8/2000 Adelman ..... D21/478 6,354,841 B1 * 3/2002 Bradt ..... G09B 19/12 434/394
(72) Inventors: <b>Paul Maxted</b> , Bristol (GB); <b>Stuart Howell</b> , Bristol (GB)	D480,116 S * 9/2003 Collins ..... D21/479 D589,708 S * 4/2009 Marek ..... D6/302 D611,985 S * 3/2010 Puglisi ..... D19/136 D627,550 S * 11/2010 Zhang ..... D2/961 8,020,867 B2 * 9/2011 Cheng ..... A63F 9/10 273/156
(73) Assignee: <b>RENISHAW PLC</b> , Wotton-Under-Edge (GB)	

(\*\*) Term: **14 Years**

(Continued)

(21) Appl. No.: **29/506,251**

**OTHER PUBLICATIONS**

(22) Filed: **Oct. 14, 2014**

<<https://www.youtube.com/watch?v=mYsAEwbEqyE>> uploaded on May 26, 2014.

(30) **Foreign Application Priority Data**

Apr. 11, 2014 (EP) .....	002445510-0001
Apr. 11, 2014 (EP) .....	002445510-0002
Apr. 11, 2014 (EP) .....	002445510-0003
Apr. 11, 2014 (EP) .....	002445510-0004

*Primary Examiner* — Ian Simmons

*Assistant Examiner* — Mark Cavanna

(74) *Attorney, Agent, or Firm* — Oliff PLC

(51) **LOC (10) Cl.** ..... **19-07**

(52) **U.S. Cl.**  
USPC ..... **D19/62**

(57) **CLAIM**

(58) **Field of Classification Search**

USPC ..... D19/59-64, 136; 434/187, 205, 211, 434/213-216, 304, 394; D21/577, D21/622-623, 632, 648, 47-480; 273/153 R, 157 R, 155-156, 149 R; 446/97, 292, 321; D30/121; 29/108; D6/302; D2/961; D10/8, 64, 74

CPC ..... A63F 9/10; A63F 9/1011; A63F 9/0666; G09B 1/06; G09B 19/12; G09B 19/02; G09B 23/02; G09B 23/00; G09B 23/04; G09B 25/02; A63H 3/16; A63H 7/04

See application file for complete search history.

The ornamental design for a metrology training device, as shown and described.

**DESCRIPTION**

FIG. 1 is a top, front, right-side perspective view of the metrology training device;  
 FIG. 2 is a front plan view thereof;  
 FIG. 3 is a back plan view thereof;  
 FIG. 4 is a left-side elevational view thereof;  
 FIG. 5 is a right-side elevational view thereof;  
 FIG. 6 is a top elevational view thereof; and,  
 FIG. 7 is a bottom elevational view thereof.

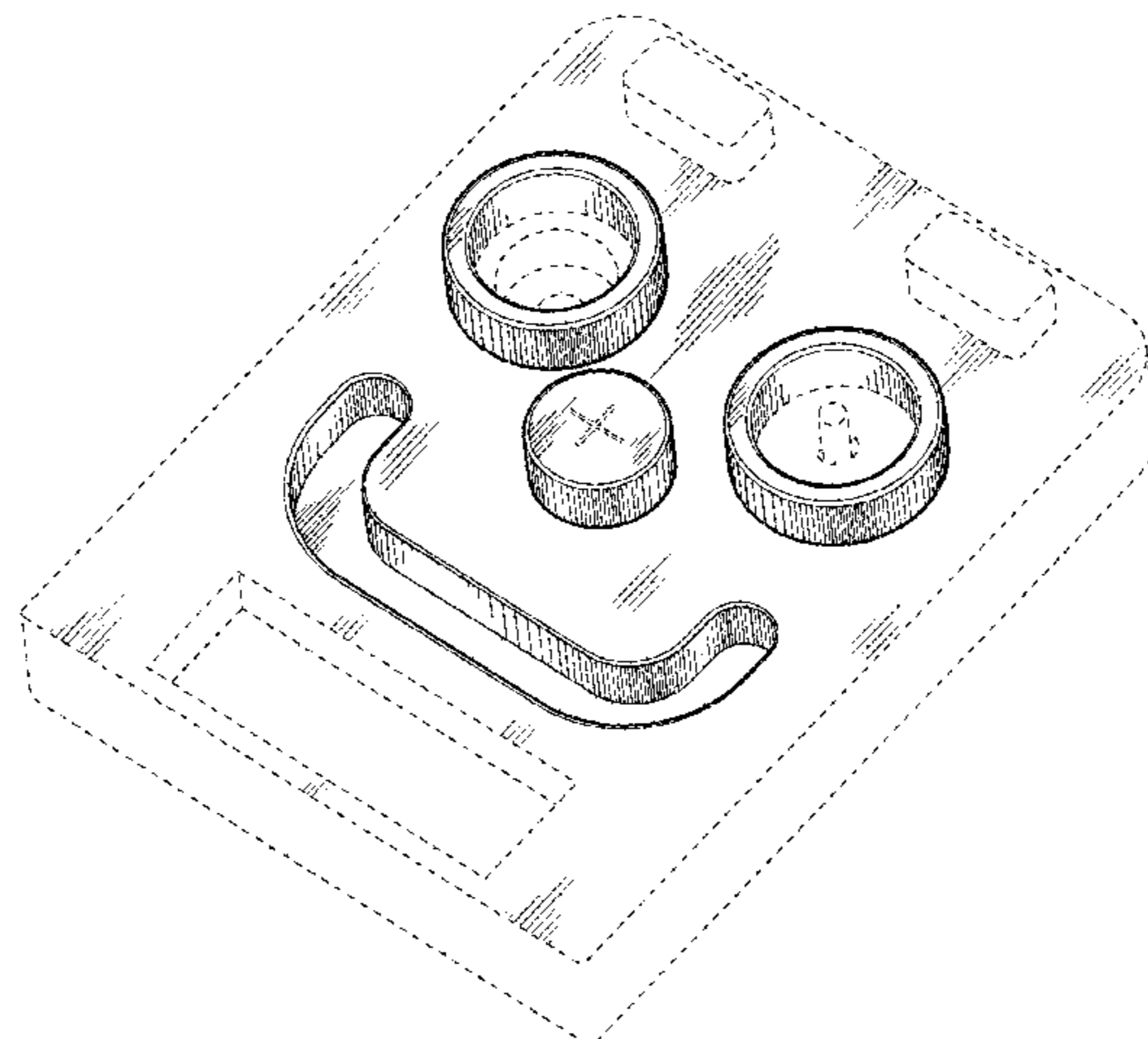
The broken lines depict portions that form no part of the claimed design.

(56) **References Cited**

**U.S. PATENT DOCUMENTS**

D193,659 S * 9/1962 Matricardi .....	D19/64
D219,216 S * 11/1970 Speers .....	434/304

**1 Claim, 5 Drawing Sheets**



(56)

**References Cited**

U.S. PATENT DOCUMENTS

8,602,833	B2 *	12/2013	Binder	.....	A63F 9/1011
					273/149 R
D698,095	S *	1/2014	Paculdo	.....	D30/121
D734,896	S *	7/2015	Mam	.....	D29/108
D737,905	S *	9/2015	Klemm	.....	D21/480
D754,801	S *	4/2016	Fox	.....	D21/480
D759,166	S *	6/2016	Fox	.....	D21/480
9,403,084	B2 *	8/2016	Klemm	.....	A63F 9/0666
2005/0184459	A1 *	8/2005	Marantz	.....	A63F 9/10
					273/157 R
2005/0200076	A1 *	9/2005	Wu	.....	A63F 9/10
					273/157 R
2007/0164513	A1 *	7/2007	Gelman	.....	A63F 9/10
					273/156

\* cited by examiner

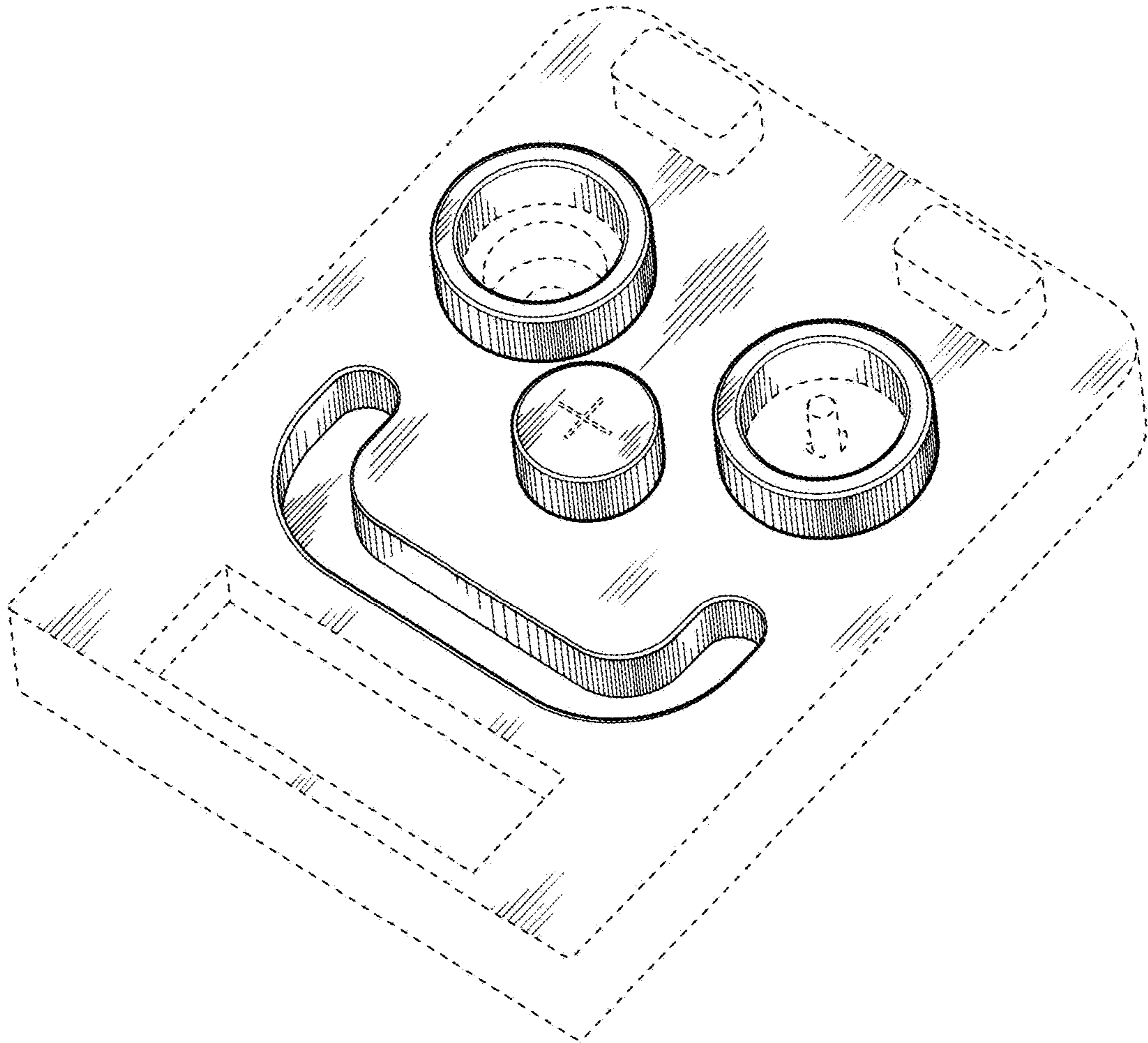


FIG. 1

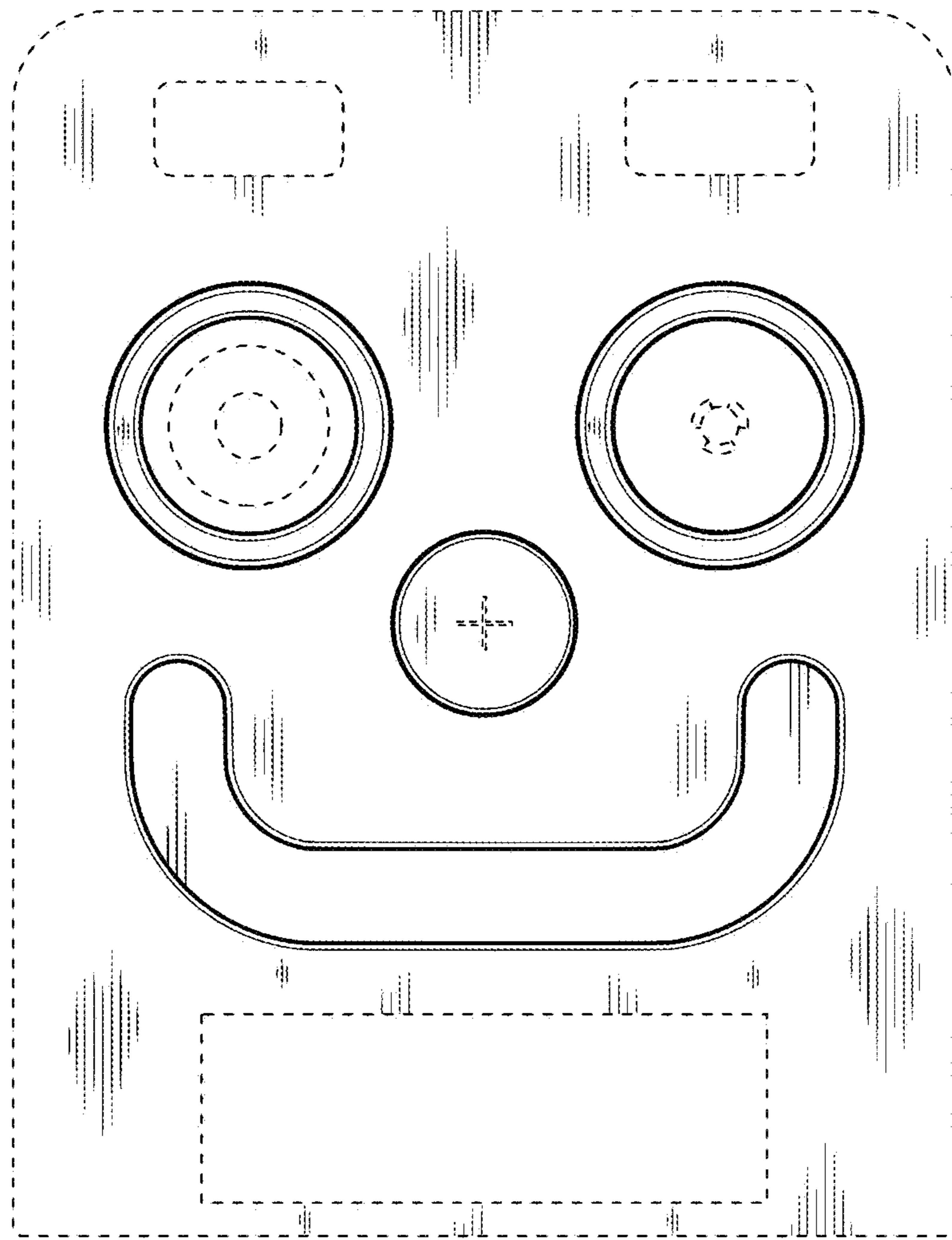


FIG. 2

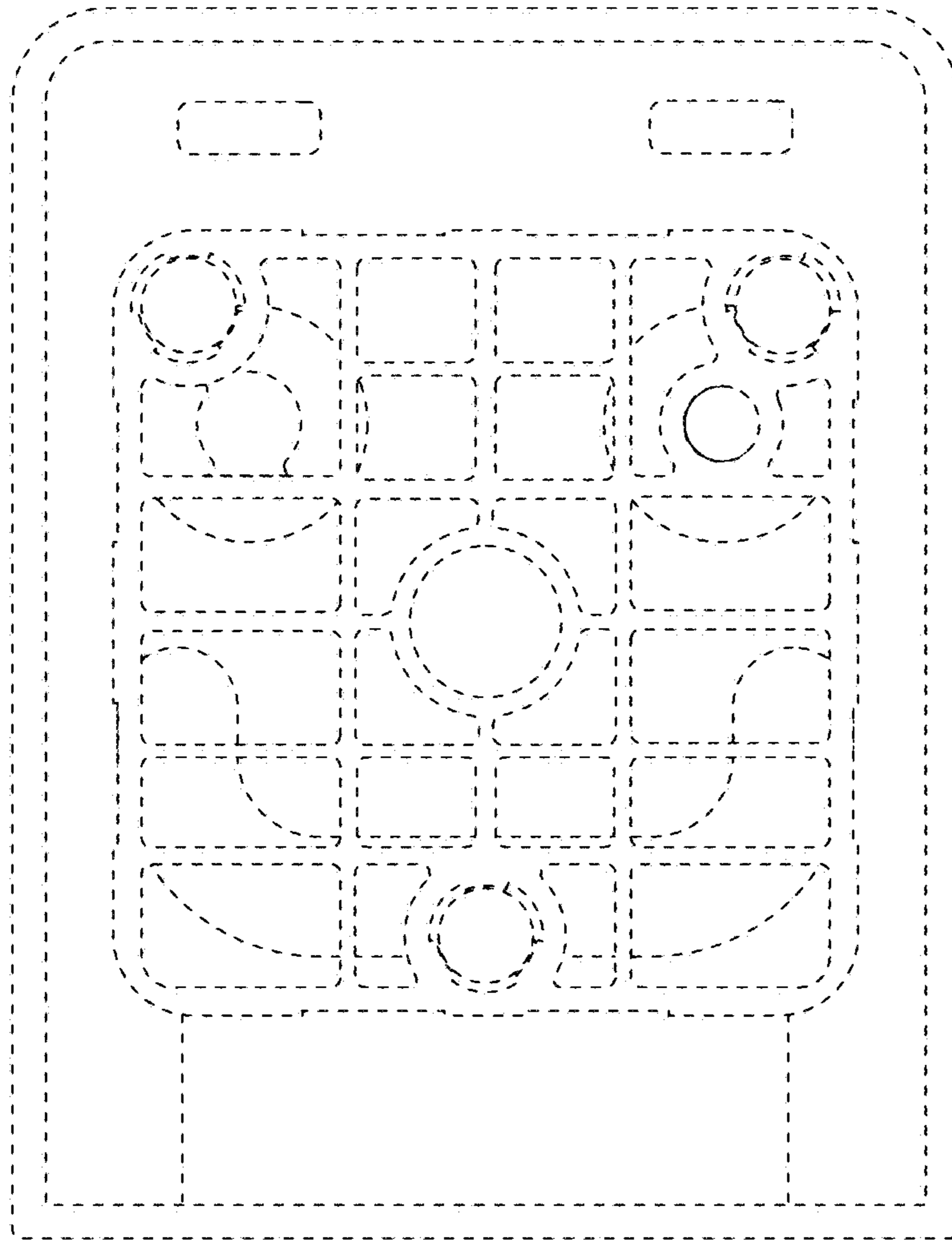


FIG. 3



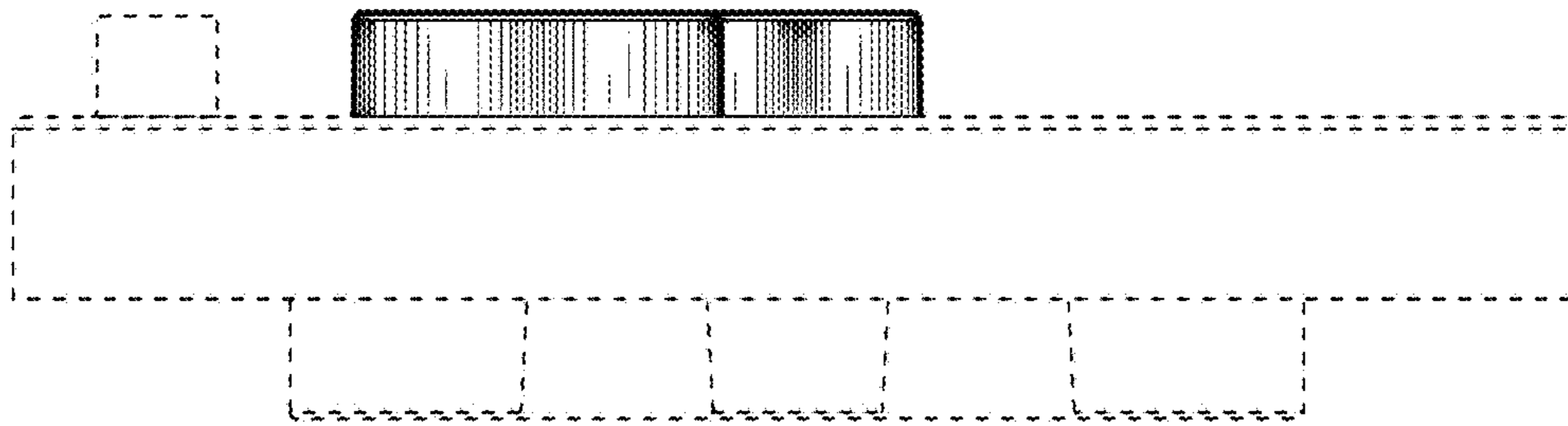


FIG. 4

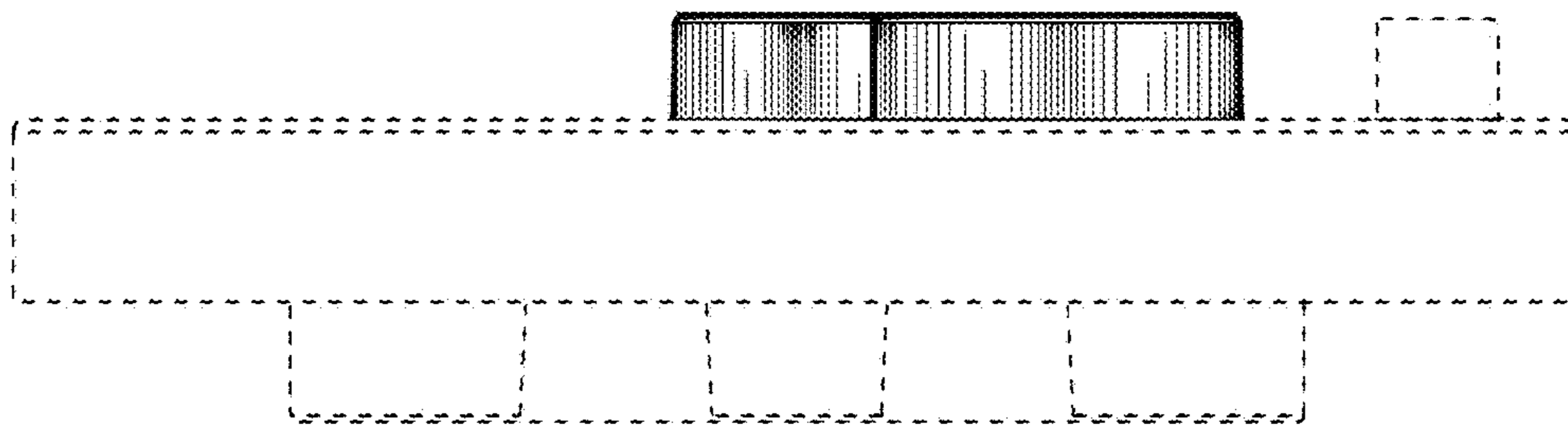


FIG. 5

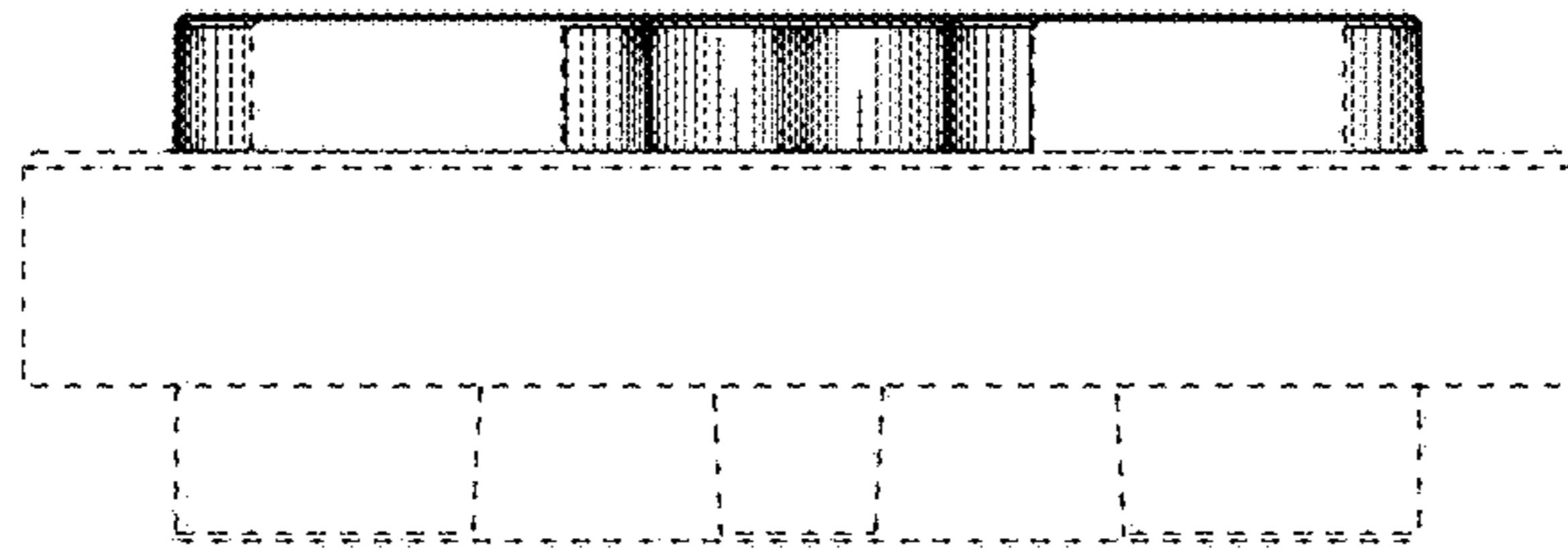


FIG. 6

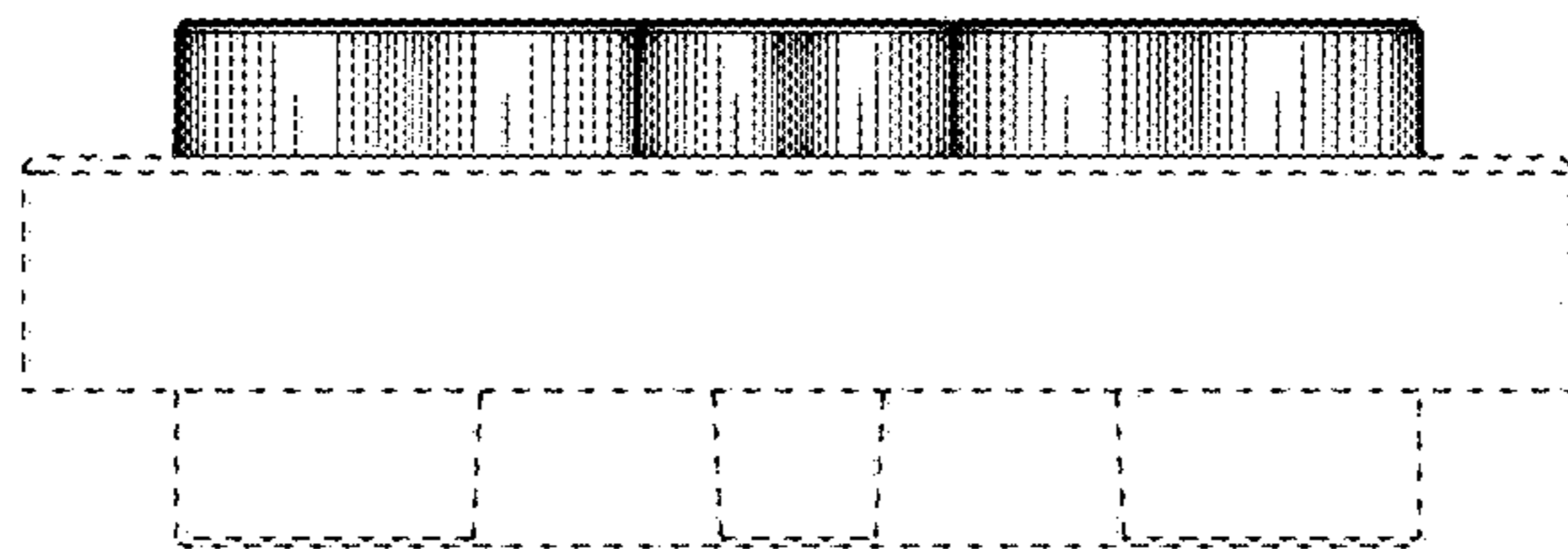


FIG. 7